

SYSTEM AND METHOD FOR MONITORING DEFECTS IN STRUCTURES

ABSTRACT

[0039] A system and method for monitoring defects in a structure are provided. The system includes a power supply for supplying an electric current to a monitoring area of the structure and a reference; a measurement circuit for measuring a potential drop across at least two contact points of the monitoring area and at least two contact points of the reference; and a processor adapted to determine a ratio of the monitoring area potential drop to the reference potential drop indicative of a percentage change in a thickness of the structure. The method includes the steps of supplying the current to the monitoring area and the reference; measuring a first potential drop across the monitoring area and the reference; and determining the ratio indicative of the percentage change in the thickness of the structure.